

**AMENDMENTS TO THE CLAIMS**

**This listing of claims will replace all prior versions and listings of claims in the application:**

**LISTING OF CLAIMS:**

1. - 7. (canceled).

8. (new): A method for coating a resist liquid on a substrate in a clean room with a downflow of a gas, comprising:

rising, by a capillary phenomenon, the resist liquid stored below a surface of the substrate to be coated, the surface facing downward;

making the resist liquid contact with the surface via a nozzle;

coating the resist liquid on the surface by moving the substrate in a direction to make the nozzle scan along the surface; and

drying the coated surface,

wherein the drying step is carried out by moving the substrate in a direction opposite to the direction of movement in the coating step, while maintaining the surface facing downward.

9. (new): The method of Claim 8, wherein the drying is carried out by moving the substrate at a speed so that the uneven drying of the coated surface caused by the eddy of the downflow gas at the surface is reduced.

10. (new): The method of Claim 9, wherein the drying is carried out by moving the substrate at a speed of 1.5m/min or lower.

11. (new): The method of Claim 9, wherein the drying is carried out by moving the substrate at a speed of 0.01 to 0.08 m/min.

12. (new): A method of manufacturing a photomask which comprises a process of coating a resist liquid on a substrate in a clean room with a downflow of a gas, comprising:

rising, by a capillary phenomenon, the resist liquid stored below a surface of the substrate to be coated, the surface facing downward;

making the resist liquid contact with the surface via a nozzle;

coating the resist liquid on the surface by moving the substrate in a direction to make the nozzle scan along the surface; and

drying the coated surface,

wherein the drying step is carried out by moving the substrate in a direction opposite to the direction of movement in the coating step, while maintaining the surface facing downward.

13. (new): The method of Claim 12, wherein the drying is carried out by moving the substrate at a speed so that the uneven drying of the coated surface caused by the eddy of the downflow gas at the surface is reduced.

14. (new): The method of Claim 13 wherein the drying is carried out by moving the substrate at a speed of 1.5m/min or lower.